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Hatakeyama et al.(10) **Pub. No.: US 2021/0033970 A1**(43) **Pub. Date: Feb. 4, 2021**(54) **RESIST COMPOSITION AND PATTERNING
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A resist composition comprising a base polymer and a quencher in the form of an ammonium salt consisting of an ammonium cation having an iodized aromatic ring bonded to the nitrogen atom via a C₁-C₂₀ hydrocarbylene group which may contain an ester bond or ether bond and a carboxylate anion having an iodized or brominated hydrocarbyl group offers a high sensitivity and minimal LWR or improved CDU, independent of whether it is of positive or negative tone.